



2818

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

TUE NGUYEN

Application No.: 09/898,439

Filed: July 5, 2001

For: Plasma semiconductor processing system  
and method

Examiner: Hoang, Quoc Dinh

Art Unit: 2818

AMENDMENT

*#6/2*  
*w/ drawings.*  
*Marsha*  
*2/4/03*

RECEIVED  
FEB -5 2003  
TECHNOLOGY CENTER 2800

Assistant Commissioner for Patents

Washington, D.C. 20231

Sir:

In response to the Office Action dated October 25, 2002, please amend the  
above-referenced application as follows.

IN THE DRAWING:

In Fig. 1A, please add reference 100 to show the plasma processing system,  
reference 106 to show the plasma excitation circuit, reference 110 to show the plasma  
generator. A new drawing of Fig. 1A is included.